

L Number	Hits	Search Text	DB	Time stamp
1	260	electroplating adj3 mask	USPAT; EPO; JPO; DERWENT	2003/06/20 14:22
2	0	(electroplating adj3 mask) and PECVD	USPAT; EPO; JPO; DERWENT	2003/06/20 14:24
3	188	438/674.ccls.	USPAT; EPO; JPO; DERWENT	2003/06/20 14:24
4	1	(electroplating adj3 mask) and 438/674.ccls.	USPAT; EPO; JPO; DERWENT	2003/06/20 14:25
5	50475	electroplat\$3	USPAT; EPO; JPO; DERWENT	2003/06/20 14:26
6	37	electroplat\$3 and 438/674.ccls.	USPAT; EPO; JPO; DERWENT	2003/06/20 14:27
7	15	(electroplat\$3 and 438/674.ccls.) and trench	USPAT; EPO; JPO; DERWENT	2003/06/20 14:34
8	106	438/674.ccls. and mask\$3	USPAT; EPO; JPO; DERWENT	2003/06/20 14:41
9	22	(438/674.ccls. and mask\$3) and electroplat\$3	USPAT; EPO; JPO; DERWENT	2003/06/20 14:45
10	52633	trench	USPAT; EPO; JPO; DERWENT	2003/06/20 14:46
11	824802	copper tantalum titanium tungsten	USPAT; EPO; JPO; DERWENT	2003/06/20 14:46
12	9812	(copper tantalum titanium tungsten) and trench	USPAT; EPO; JPO; DERWENT	2003/06/20 14:46
13	588262	"aluminum nitride" "Silicon Nitride" "tantalum nitride" "titanium nitride" aln SiN Tan Tin "Aluminium oxide" "Silicon oxide" "Tantalum oxide" "Titanium oxide" Al2O3 SiO2 TaO TiO	USPAT; EPO; JPO; DERWENT	2003/06/20 14:48
14	7282	("aluminum nitride" "Silicon Nitride" "tantalum nitride" "titanium nitride" aln SiN Tan Tin "Aluminium oxide" "Silicon oxide" "Tantalum oxide" "Titanium oxide" Al2O3 SiO2 TaO TiO) and ((copper tantalum titanium tungsten) and trench)	USPAT; EPO; JPO; DERWENT	2003/06/20 14:48
15	806	((("aluminum nitride" "Silicon Nitride" "tantalum nitride" "titanium nitride" aln SiN Tan Tin "Aluminium oxide" "Silicon oxide" "Tantalum oxide" "Titanium oxide" Al2O3 SiO2 TaO TiO) and ((copper tantalum titanium tungsten) and trench)) and electroplat\$3	USPAT; EPO; JPO; DERWENT	2003/06/20 14:48
16	760	((("aluminum nitride" "Silicon Nitride" "tantalum nitride" "titanium nitride" aln SiN Tan Tin "Aluminium oxide" "Silicon oxide" "Tantalum oxide" "Titanium oxide" Al2O3 SiO2 TaO TiO) and ((copper tantalum titanium tungsten) and trench)) and electroplat\$3) and (partial portion exposed)	USPAT; EPO; JPO; DERWENT	2003/06/20 14:49

17	205	(((("aluminum nitride" "Silicon Nitride" "tantalum nitride" "titanium nitride" aln SiN Tan Tin "Aluminium oxide" "Silicon oxide" "Tantalum oxide" "Titanium oxide" Al2O3 SiO2 TaO TiO) and ((copper tantalum titanium tungsten) and trench)) and electroplat\$3) and (partial portion exposed)) and PECVD	USPAT; EPO; JPO; DERWENT	2003/06/20 14:49
18	1727061	(((("aluminum nitride" "Silicon Nitride" "tantalum nitride" "titanium nitride" aln SiN Tan Tin "Aluminium oxide" "Silicon oxide" "Tantalum oxide" "Titanium oxide" Al2O3 SiO2 TaO TiO) and ((copper tantalum titanium tungsten) and trench)) and electroplat\$3) and (partial portion exposed)) and PECVD) and copper cu Platinum Pt Palladium Pd Nickel Ni	USPAT; EPO; JPO; DERWENT	2003/06/20 14:50
19	203	(((("aluminum nitride" "Silicon Nitride" "tantalum nitride" "titanium nitride" aln SiN Tan Tin "Aluminium oxide" "Silicon oxide" "Tantalum oxide" "Titanium oxide" Al2O3 SiO2 TaO TiO) and ((copper tantalum titanium tungsten) and trench)) and electroplat\$3) and (partial portion exposed)) and PECVD) and copper cu Platinum Pt Palladium Pd Nickel Ni and (((("aluminum nitride" "Silicon Nitride" "tantalum nitride" "titanium nitride" aln SiN Tan Tin "Aluminium oxide" "Silicon oxide" "Tantalum oxide" "Titanium oxide" Al2O3 SiO2 TaO TiO) and ((copper tantalum titanium tungsten) and trench)) and electroplat\$3) and (partial portion exposed)) and PECVD)	USPAT; EPO; JPO; DERWENT	2003/06/20 14:50
20	142828	(((("aluminum nitride" "Silicon Nitride" "tantalum nitride" "titanium nitride" aln SiN Tan Tin "Aluminium oxide" "Silicon oxide" "Tantalum oxide" "Titanium oxide" Al2O3 SiO2 TaO TiO) and ((copper tantalum titanium tungsten) and trench)) and electroplat\$3) and (partial portion exposed)) and PECVD) and copper cu Platinum Pt Palladium Pd Nickel Ni and (((("aluminum nitride" "Silicon Nitride" "tantalum nitride" "titanium nitride" aln SiN Tan Tin "Aluminium oxide" "Silicon oxide" "Tantalum oxide" "Titanium oxide" Al2O3 SiO2 TaO TiO) and ((copper tantalum titanium tungsten) and trench)) and electroplat\$3) and (partial portion exposed)) and PECVD)) and "side wall" sidewall	USPAT; EPO; JPO; DERWENT	2003/06/20 14:51

21	76	(((((((("aluminum nitride" "Silicon Nitride" "tantalum nitride" "titanium nitride" aln SiN Tan Tin "Aluminium oxide" "Silicon oxide" "Tantalum oxide" "Titanium oxide" Al2O3 SiO2 TaO TiO) and ((copper tantalum titanium tungsten) and trench)) and electroplat\$3) and (partial portion exposed)) and PECVD) and copper cu Platinum Pt Palladium Pd Nickel Ni) and (((("aluminum nitride" "Silicon Nitride" "tantalum nitride" "titanium nitride" aln SiN Tan Tin "Aluminium oxide" "Silicon oxide" "Tantalum oxide" "Titanium oxide" Al2O3 SiO2 TaO TiO) and ((copper tantalum titanium tungsten) and trench)) and electroplat\$3) and (partial portion exposed)) and PECVD)) and "side wall" sidewall) and ((((((("aluminum nitride" "Silicon Nitride" "tantalum nitride" "titanium nitride" aln SiN Tan Tin "Aluminium oxide" "Silicon oxide" "Tantalum oxide" "Titanium oxide" Al2O3 SiO2 TaO TiO) and ((copper tantalum titanium tungsten) and trench)) and electroplat\$3) and (partial portion exposed)) and PECVD) and copper cu Platinum Pt Palladium Pd Nickel Ni) and (((("aluminum nitride" "Silicon Nitride" "tantalum nitride" "titanium nitride" aln SiN Tan Tin "Aluminium oxide" "Silicon oxide" "Tantalum oxide" "Titanium oxide" Al2O3 SiO2 TaO TiO) and ((copper tantalum titanium tungsten) and trench)) and electroplat\$3) and (partial portion exposed)) and PECVD))	USPAT; EPO; JPO; DERWENT	2003/06/20 15:15
22	71881	electroless electroplat\$3	USPAT; EPO; JPO; DERWENT	2003/06/20 15:15
23	260	(electroless electroplat\$3) and (electroplating adj3 mask)	USPAT; EPO; JPO; DERWENT	2003/06/20 15:29
24	3	"6432820"	USPAT; EPO; JPO; DERWENT	2003/06/20 15:29